SU-8 Hotplates

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Safety
- Surfaces can be hot.

Process Restrictions
Material Restrictions
- SU-8 resists only

Parameter Restrictions
- None

Scheduling / Sign-up Restrictions
- Hotplates #1-#4 must be reserved and used in the CORAL system.
- No reservations more than 7 days in advance.
- Always reserve the tool to let others know how long to expect the tool to be in use.
- Follow any posted time limits (if applicable) on the hotplates

Requirements (Do Every Time)
- Turn the hotplate off when you are finished.
- Clean the photoresist from the backside and edge of wafers before baking.

Prohibitions (Never Do)
- Do not move the hotplates. This will unlevel them.

Common Problems

<table>
<thead>
<tr>
<th>Problem:</th>
<th>Root Cause:</th>
<th>Solution:</th>
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<tbody>
<tr>
<td>- Thickness of baked resist is uneven across the wafer</td>
<td>- Hotplate is out of level.</td>
<td>- Use the bubble level to relevel hotplates.</td>
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<tr>
<td>- Baked resist is dimpled across the wafer</td>
<td>- Airflow across the wafer is too high</td>
<td>- Never move the hotplates</td>
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<td>- Place a crystalization dish upside down over top of the wafer.</td>
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</table>

Other Comments or Cautions

Calls to staff phones will be automatically forwarded to their cell phones during accessible hours. At other times leave a message or send them an email.